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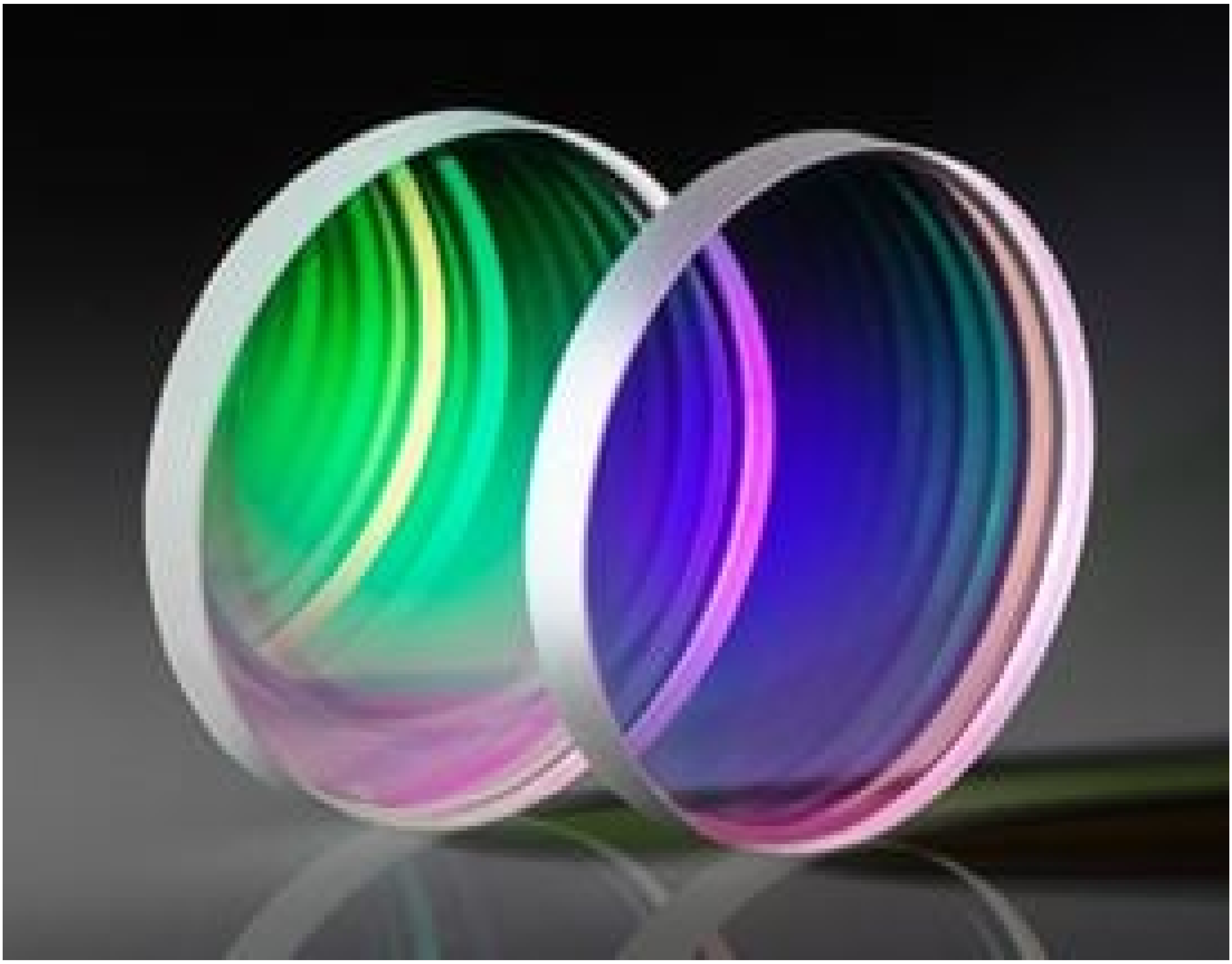
20-40nm, 50.8mm Dia, EUV/IR Dichroic Filter



Extreme Ultraviolet (EUV) Dichroic Filters

Stock **#18-280** **3 In Stock**

- 1 + **MRP ₹5,44,806**

Price inclusive of all taxes

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Volume Pricing	
Qty 1+	**₹5,44,806** each
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General

Type:
Dichroic Filter

Physical & Mechanical Properties

Diameter (mm):
50.80

Thickness (mm):
5.08 ±0.1

Parallelism (arcmin):
<5

Dimensional Tolerance (mm):

+0.0/-0.2

Optical Properties

Angle of Incidence (°):

78

Substrate:

Fused Silica (Corning 7980)

Coating:

Dielectric Multilayer AR

Reflection (%):

>40

Surface Quality:

20-10

Wavelength Range (nm):

20 - 40

Surface Figure, RMS:

<λ/10 @633nm

Regulatory Compliance

Certificate of Conformance:

View

Country of Origin:

Japan

Imported By:

Edmund Optics India Private Limited
267, Greystone Building, Second Floor,
6th Cross Rd, Binnamangala,
Stage 1, Indiranagar, Bengaluru,
Karnataka, India 560038
Phone: +91- 80-6845 0000

Product Details

- Separates EUV from the NIR Laser Source in High Harmonic Generation
- Designed for High Damage Thresholds
- Supports Applications from 10 – 40nm
- Available from Stock
- No Minimum Order Quantities, No Coating Lot Charges

Extreme Ultraviolet (EUV) Dichroic Filters, also known as beam separators, are intended for high harmonic generation applications by providing a high separation efficiency between the EUV and NIR wavelengths. Featuring a Fused Silica substrate, these filters support higher laser powers than the alternative Brewster’s angle beam separators and EUV filters. EUV Dichroic Filters feature a broad bandwidth range from 10nm to 40nm. In addition to high harmonic generation, these filters can also be used in systems that support EUV applications such as EUV lithography, EUV nanomachining, coherent diffractive imaging, and ultrafast attosecond pulse generation.

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